

METHOD AND DEVICE FOR EXPOSURE

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Abstract:

PROBLEM TO BE SOLVED: To provides method and device for exposure capable of exposing a pattern, having a fine hole diameter and patterns of rows of contact holes or mixed independent contact holes with the rows of contact holes, with a high degree of resolution (or the degree of resolution equal to L-and-S pattern employing a phase shift mask for the rows of contact holes) without exchanging any mask. SOLUTION: The mask is projected against a body to be exposed through a projection optical system by a method wherein the mask, on which the patterns of contact holes and another pattern having a size smaller than that of the pattern of the contact hole are arrayed, is irradiated by a plurality of kinds of light so that the patterns of the contact holes are resolved and the resolution of the pattern having the small size is restrained. COPYRIGHT: (C)2003,JPO

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